U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE ATTY. DOCKET NO. MI22-1670 SERIAL NO. 09/881,407 Form PTO-1449 DO BY APPLICANT APPLICANT Zhongze Wang FILING DATE GROUP June 13, 2001 U.S. PATENT DOCUMENTS Subclass *Examiner Document Filing Date Number If Appropriate AΑ 5,254,489 10/19/93 Nakata ΑB 5,464,792 11/07/95 Tseng et al. AC 5.596,218 01/21/97 Soleimani et al. AD 5,620,908 04/15/97 Inoh et al. 5,674,788 10/07/97 ΑE Wristers et al. ΑF 5,716,864 02/10/98 AG 5,960,302 09/28/99 Ma et al. Arai et al. ΑH 5,972,783 10/26/99 ΑI 5,994,749 11/30/99 Oda 6,225,151 05/01/01 ΑJ Gardner et al. 4,651,406 03/24/87 Shimizu et al. FOREIGN PATENT DOCUMENTS Document Date Country Class Subclass Translation Number Yes No 甲 ΑL WO 96/39713 12/12/96 PCT AM JP06302813A 04/09/93 Japan (Citizen Watch Co. Ltd.) AN ΑO AP OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.) Doyle et al., "Simultaneous Growth of Different Thickness Gate Oxides in Silicon CMOS Processing", IEEE Electron Device Letters, Vol. 16, Ko et al., "The Effect of Nitrogen Incorporation Into the Gate Oxide by Using Shallow Implantation of Nitrogen and Drive-in Process", 1998 IEEE, 0-7803-4932-6/98. Kurni et al., "The Effects of Nitrogen Imp nion Into P + Poly-Silicon Gate on Gate Oxide Properties, 1994 Symposium on VLSI Technology Digest of Technical Papers, pp. 107-108. Date Considered 17 Sept. 2002 **EXAMINER** *EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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